제 32회 한국반도체학술대회
The 32nd Korean Conference on Semiconductors

2025년 2월 12일(수)-14일(금) I 강원도 하이원리조트

Future Normal in Semiconductor

2025년 2월 14일(금), 15:10-17:10
Room L(하트II+III), 6층

B. Patterning (Lithography & Etch Technology) 분과

O78_[FL3-B] Etch

좌장: 채희엽 교수(성균관대학교), 이상헌 교수(이화여자대학교)

초청 FL3-B-1 15:10-15:40	Semiconductor Equipment Technology: What's Next? Dougyong Sung Mechatronics Research, Samsung Electronics Co., Ltd.
FL3-B-2 15:40-15:55	Low-temperature SiO_2 Contact Hole Etching Using C_4F_8 Plasmas 유상현[1,2], 김창구[1,2] [1]Department of Chemical Engineering, Ajou University, [2]Department of Energy Systems Research, Ajou University
FL3-B-3 15:55-16:10	High-throughput Isotropic Atomic Layer Etching of Hafnia Films Using F Radicals and Al Precursors Gyejun Cho, Jehwan Hong, Hye-Lee Kim, and Won-Jun Lee Department of Nanotechnology and Advanced Materials Engineering, Sejong University
초청 FL3-B-4 16:10-16:40	Technical Challenge and Development of HARC Etching Sang Wook Park, Jae Won Lee, Sang Heon Song, Kyung Tae Kim, Ki Jun Yun, Hoo Woong Lee, Woo June Kwon, Chung Won Seo, and Hyun Min Lee SK hynix Inc.
FL3-B-5 16:40-16:55	Investigation on the Effect of Tailored Waveform Bias on the Formation of SiO_2/Si Trench Etch Profile in SF_6/O_2/Ar Plasma Taejun Park[1], Jihoon Park[1], Ingyu Lee[1], Namkyun Kim[2], and Gon-Ho Kim[1] [1]Seoul National University, [2]Samsung Electronics Co., Ltd.
FL3-B-6 16:55-17:10	Ultrathin Ni Catalyst for CMOS-compatible Metal-assisted Chemical Etching of Si Kyunghwan Kim[1,2], Haekyun Bong[1,3], and Jungwoo Oh[1,3] [1]School of Integrated Technology, Yonsei University, [2]Center for Quantum Technology, KIST, [3]BK21 Graduate Program in Intelligent Semiconductor Technology, Yonsei University